

# Sub-pixel characterization of innovative 3D trench-design silicon pixel sensors using ultra-fast laser-based testing equipment

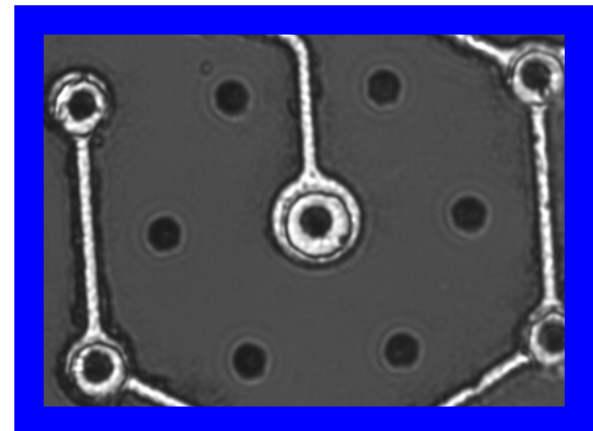
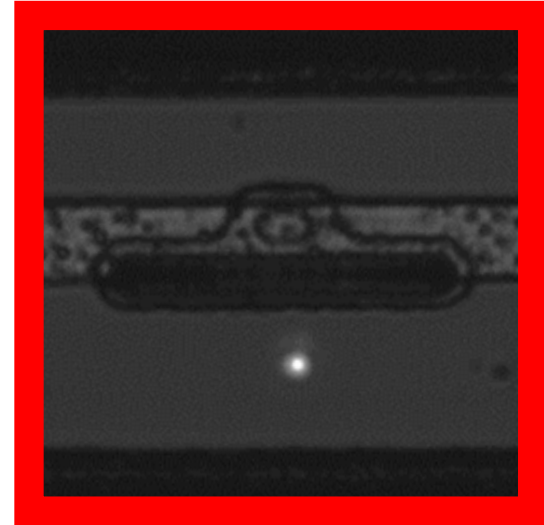
16th (Virtual) "Trento" Workshop on Advanced Silicon Radiation Detectors

A. Lampis on behalf of the TimeSPOT team



# Outline

- Sensor non uniformity contribution to a charged particle detector time resolution
- Laser based setup
- Sensor characterization:
  - Amplitude maps
  - Time of Arrival maps
- Comparison between trench sensor and column sensor



# Sensor non-uniformity $\sigma_{un}$

The sensor signal is produced by the drift of the charge carriers created along the path of the (charged) particle across the pixel volume, this charge motion induces an instantaneous current at the readout electrode defined as

$$i = q \vec{E}_w \cdot \vec{v}_d$$

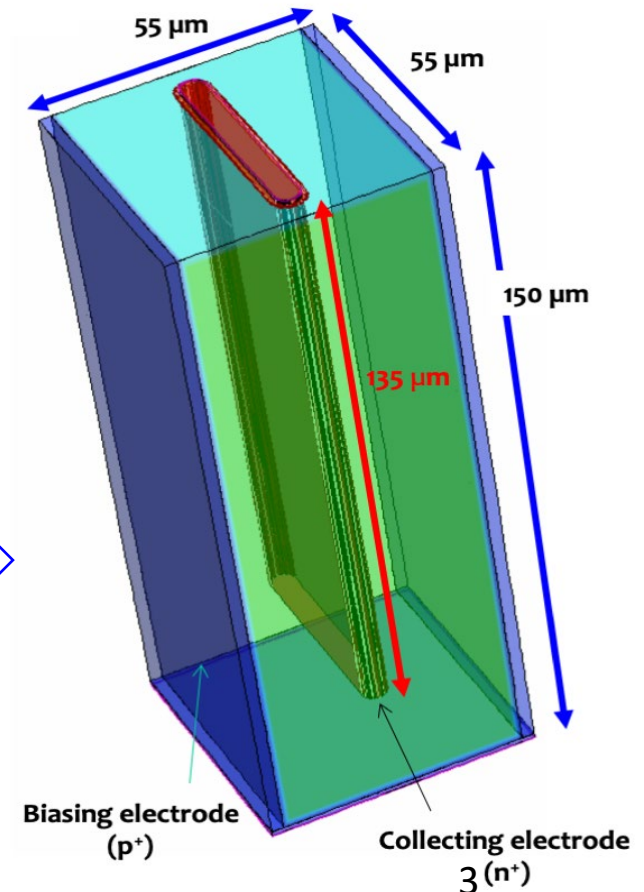
weighting field

carrier's drift velocity

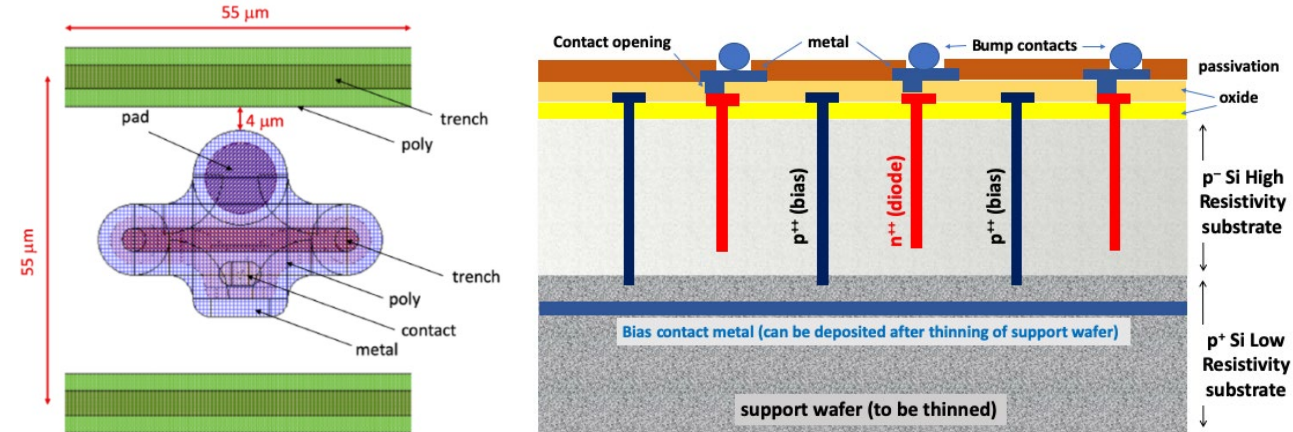
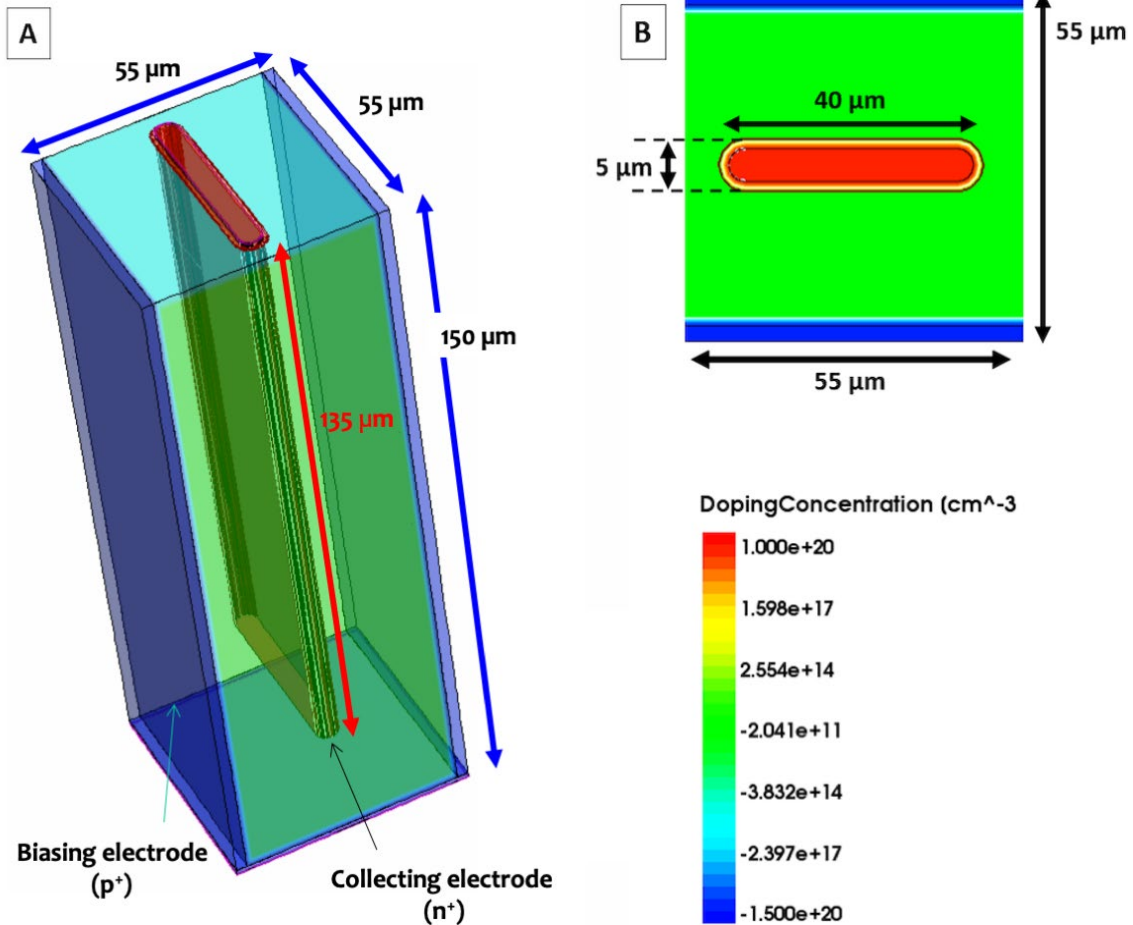
If  $\vec{E}_w \cdot \vec{v}_d$  is as uniform as possible inside the active volume the signals do not depend on where the charged particle has crossed the detector:

- $\vec{E}_w$  uniform by design
- work in a velocity saturation regime

Trench geometry



# The trench-type TimeSPOT 3D pixels

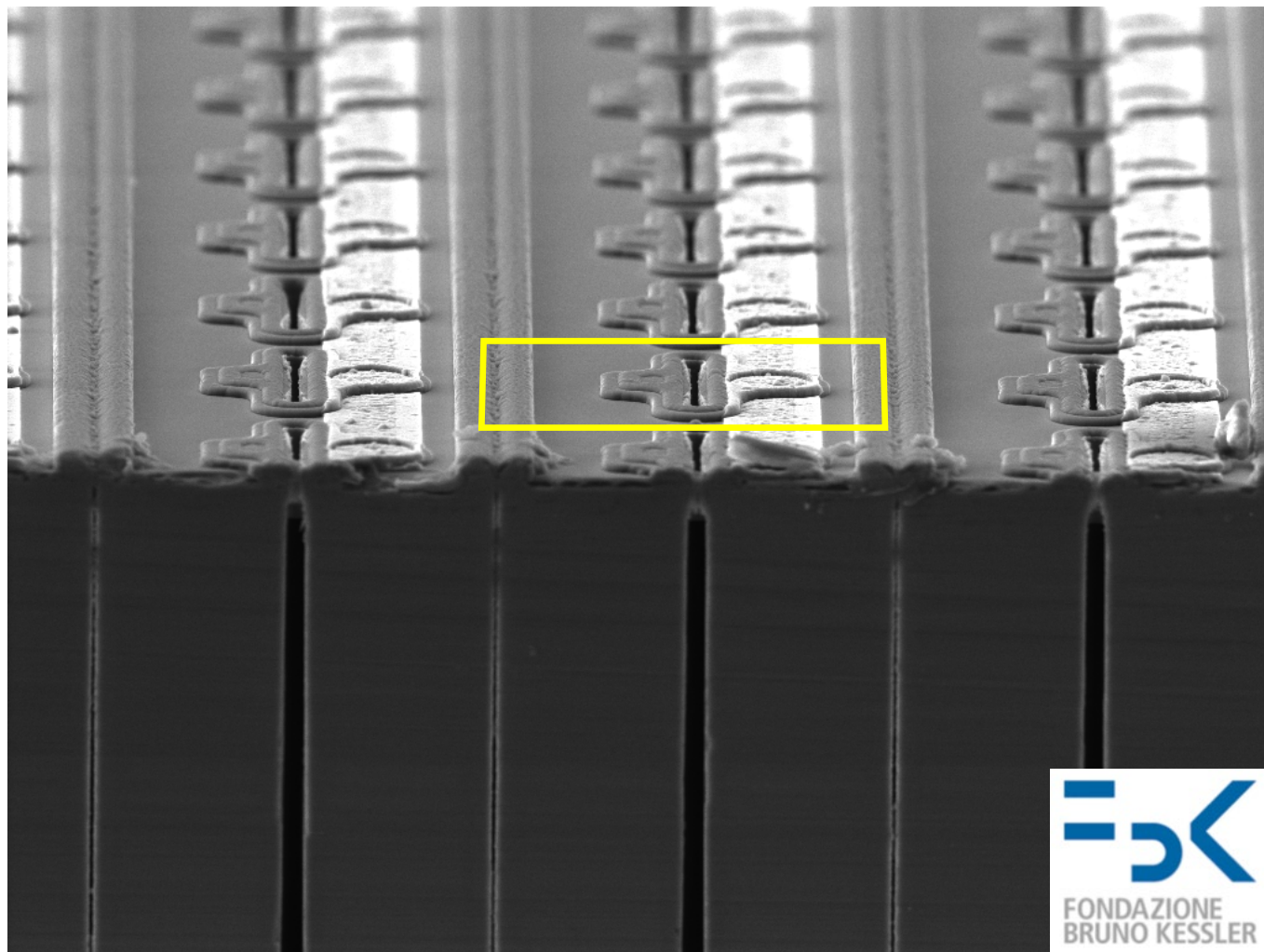
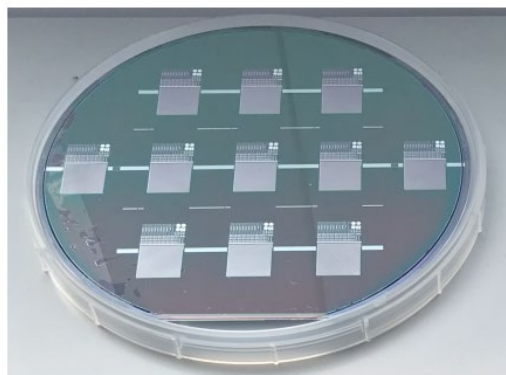
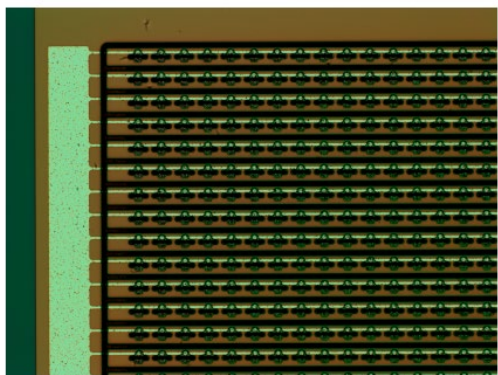
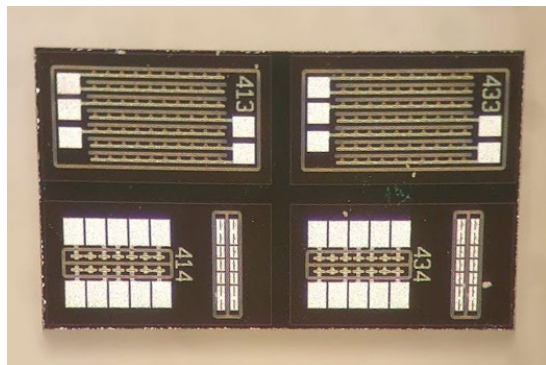
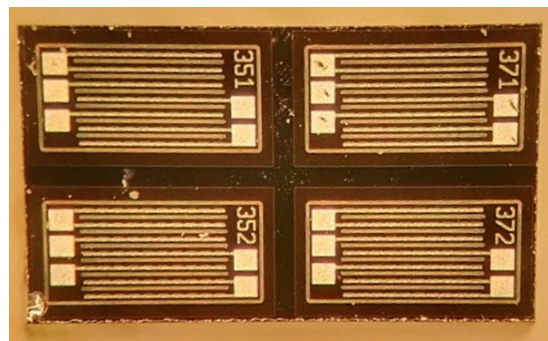


- $55\ \mu\text{m} \times 55\ \mu\text{m}$  pixels (to be compatible with existing FEE, for example the Timepix family)
- In each pixel a  $40\ \mu\text{m}$  long  $n^{++}$  trench is placed between continuous  $p^{++}$  trenches used for the bias
- $150\ \mu\text{m}$ -thick active thickness, on a  $350\ \mu\text{m}$ -thick support wafer
- The collection electrode is  $135\ \mu\text{m}$  deep

# TimeSPOT silicon sensor

First batch produced in 2019 at Fondazione Bruno Kessler (FBK, Trento, Italy)

Many devices fabricated (single, double pixels, pixel-strips, 256x256 pixel matrices)



SEM HV: 10.0 kV	WD: 11.59 mm		VEGA3 TESCAN
View field: 176 $\mu$ m	Det: SE	50 $\mu$ m	
SEM MAG: 1.57 kx	Date(m/d/y): 10/29/19		FBK Micro-nano Facility

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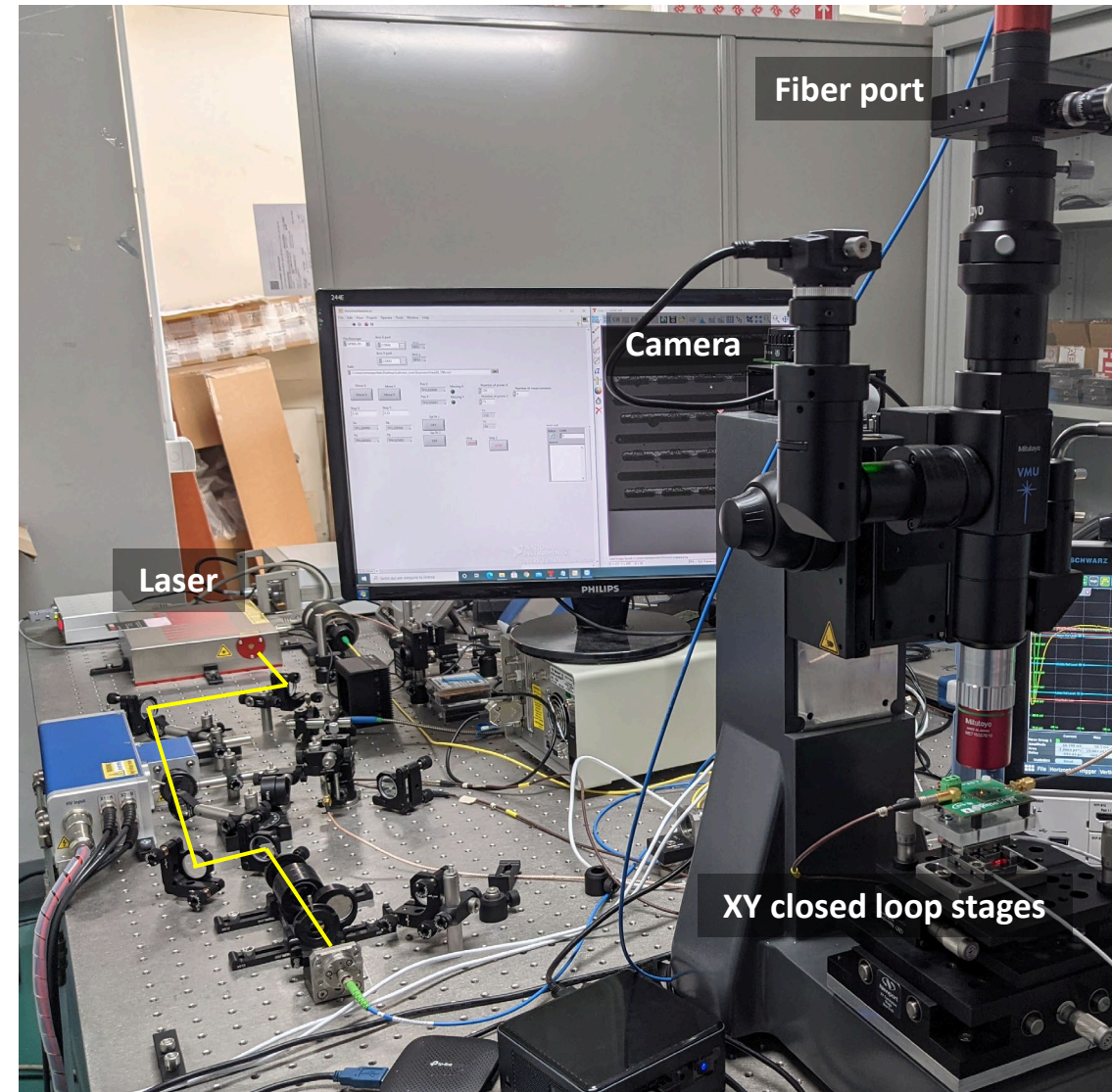
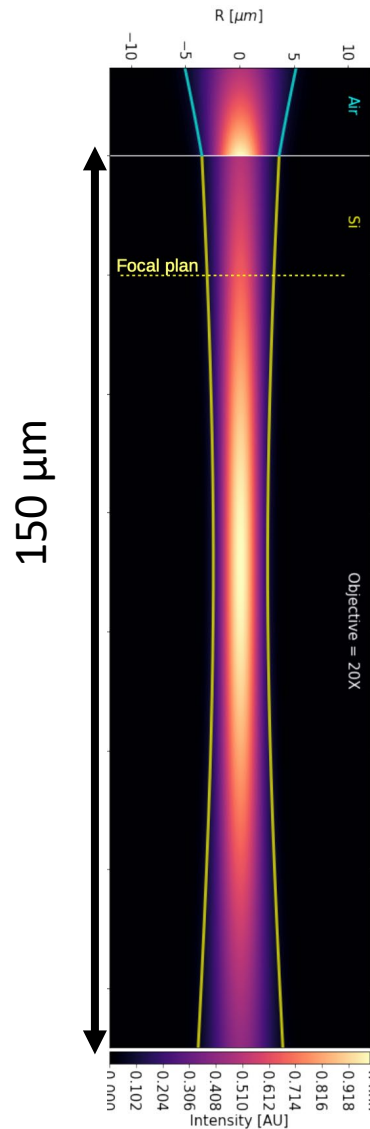
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# Laser-based setup

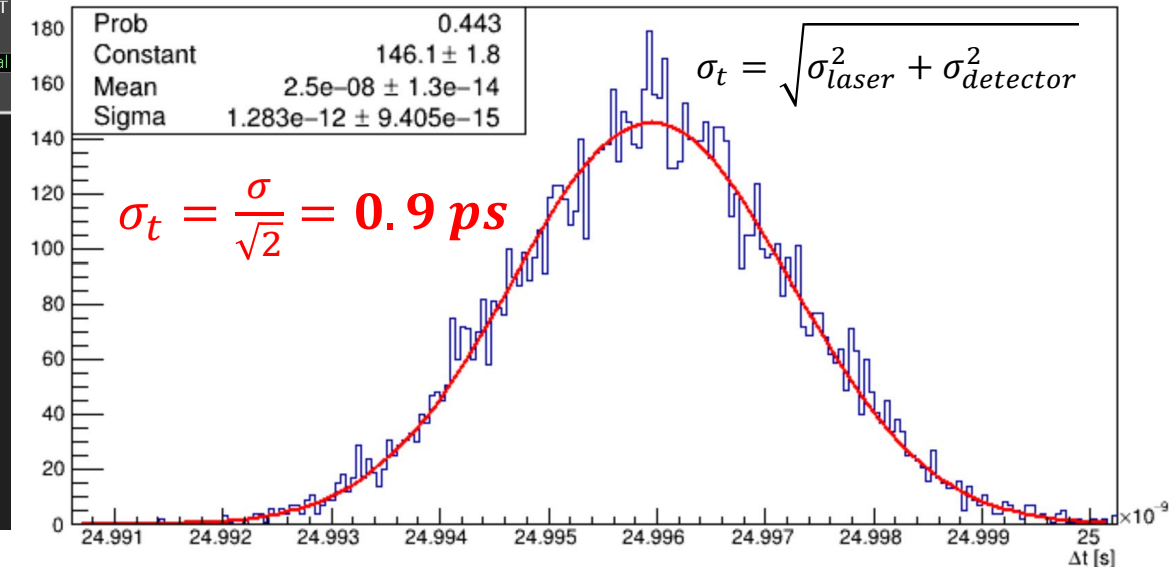
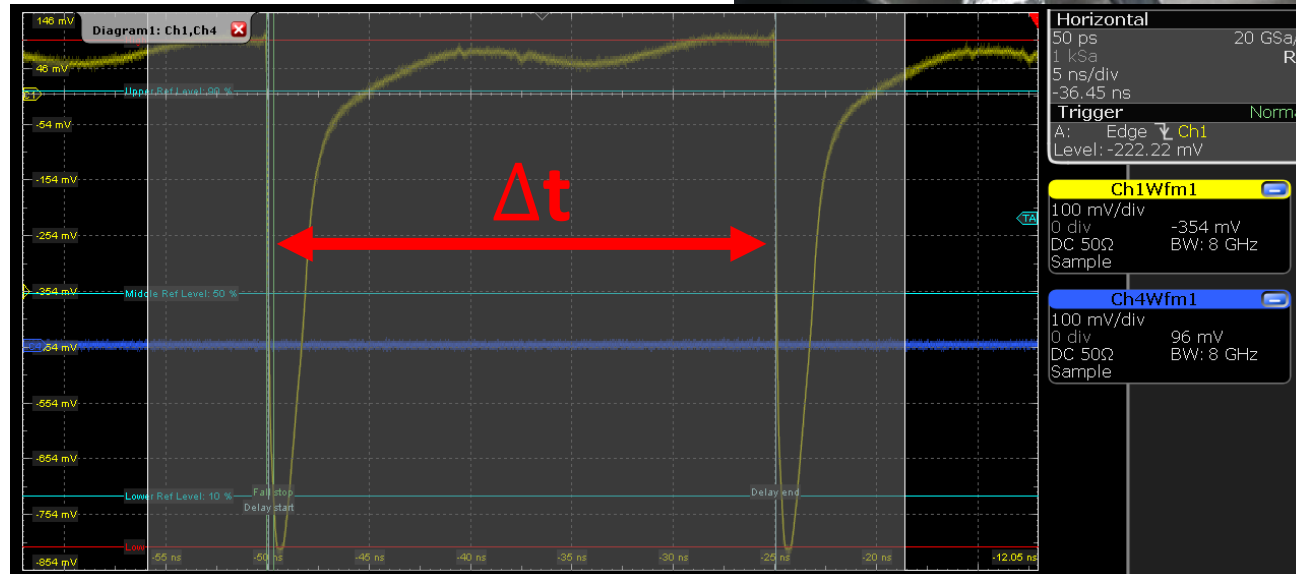
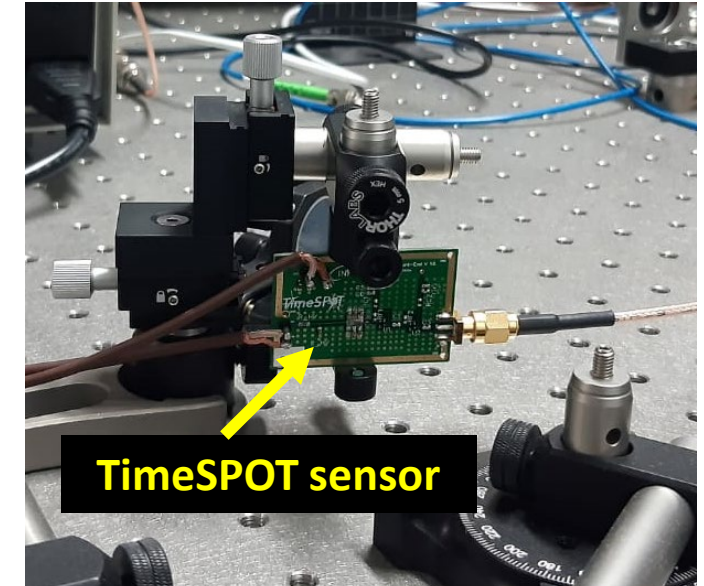
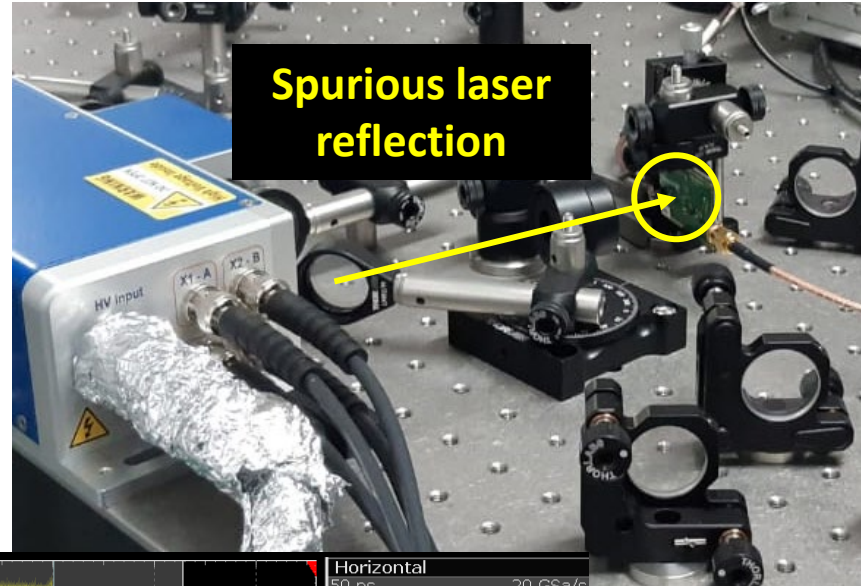
Laser setup allows to emulate the energy deposit of a MIP passing through the sensor

- Pulsed laser:
  - IR Laser (1030 nm), FWHM < 200 fs
- Optical fiber from laser to **microscope**.
- **Focused spot of  $\sim 5 \mu m$**
- Observation **camera**
- **XY closed loop stages**
- **Optical laser time reference: accuracy <1ps**



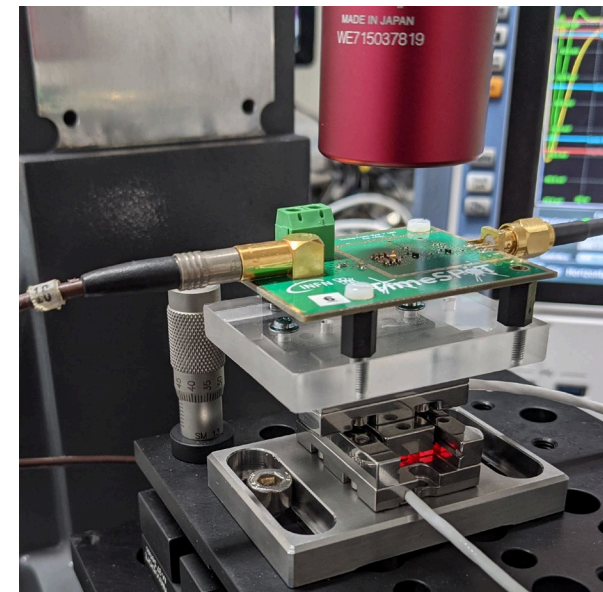
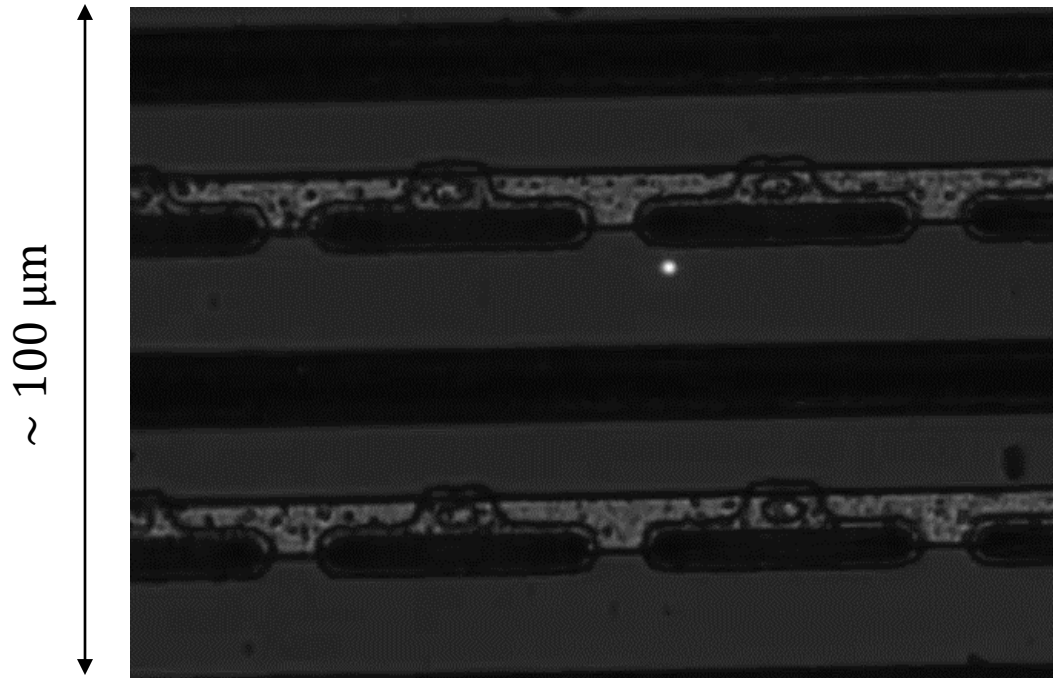
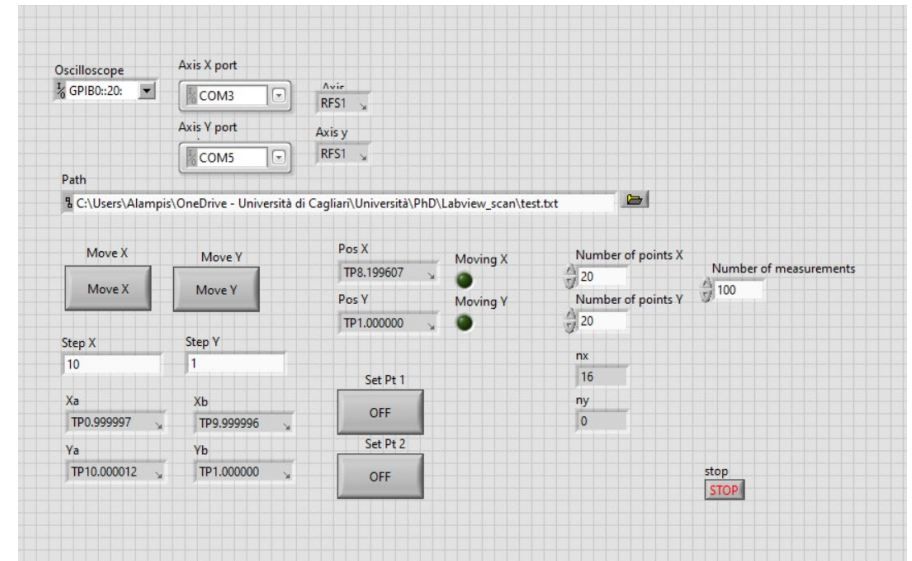
# Optical laser time reference

The time reference is itself a TimeSPOT 3D sensor but stimulated with high intensity ( $\sim 10$  MIP)



# The sensor scan

- Labview software to perform the sensor scan:
  - XY closed loop stages move the sensor with respect to the laser beam → **scanning step  $1\ \mu\text{m}$**
  - Oscilloscope acquires sensor's waveforms and perform the measurements



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# Measurements

- Measurements performed via 8 GHz oscilloscope 20 GSa/s

- Averaged waveform to reduce electronic noise contribution:  $\longrightarrow$

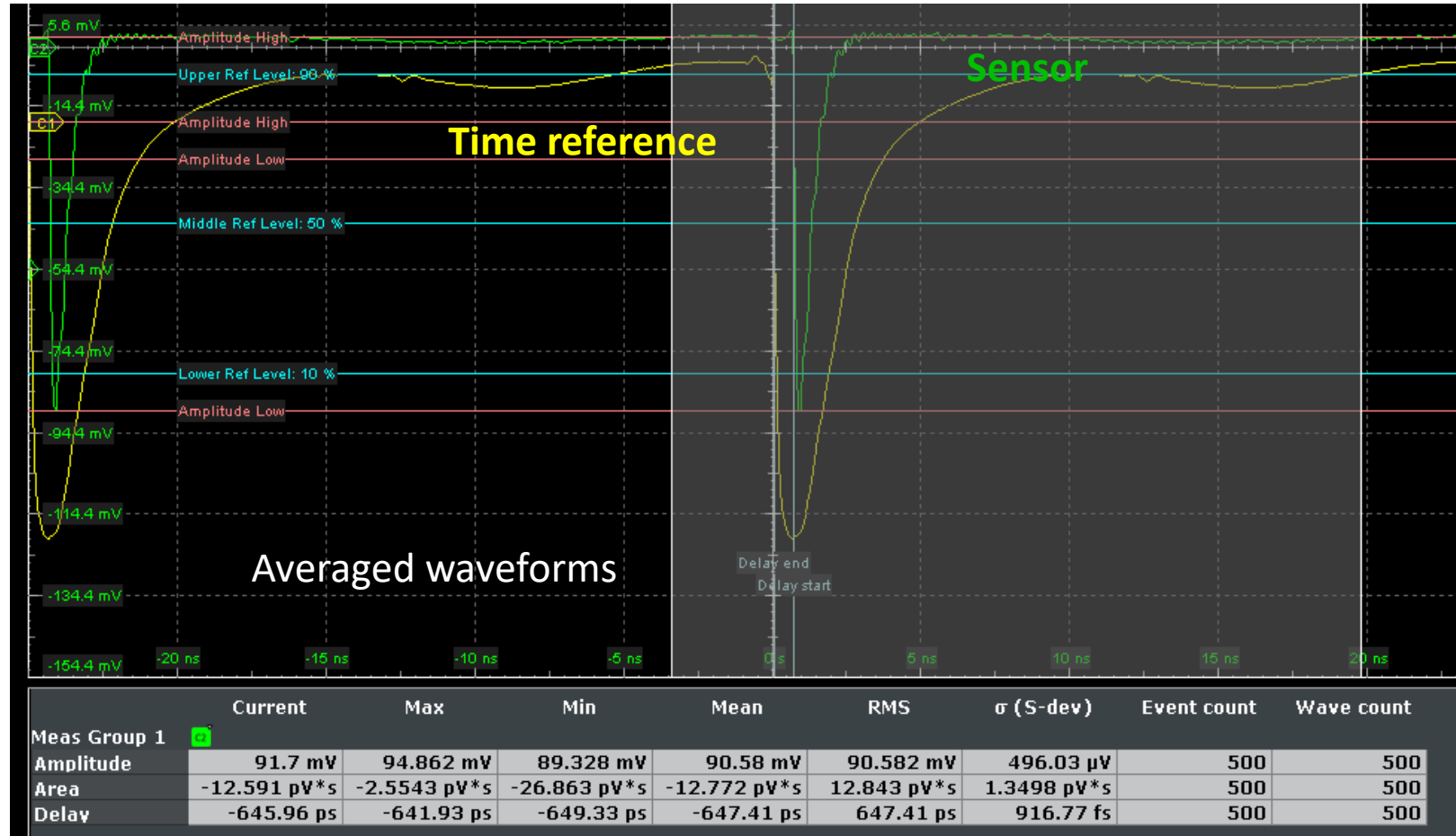
$$\sigma = \sqrt{\sigma_{un}^2 + \sigma_{ej}^2}$$

- For each position we measured:

- Sensor signal amplitude
- Time of Arrival (ToA) of laser pulses

$$\text{ToA} = t_{sensor} - t_{ref}$$

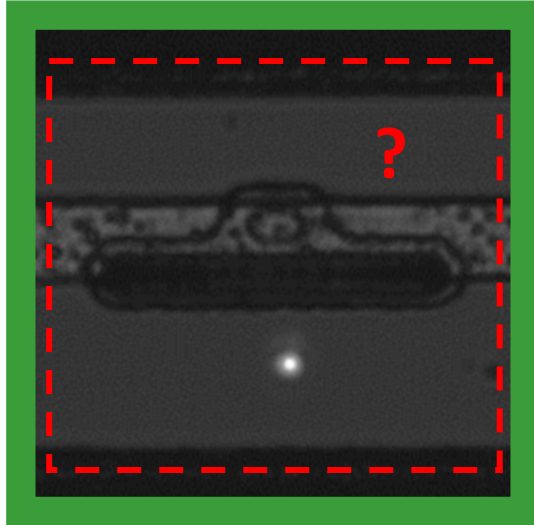
$t_{sensor}$  and  $t_{ref}$  by CFD @ 50% of amp



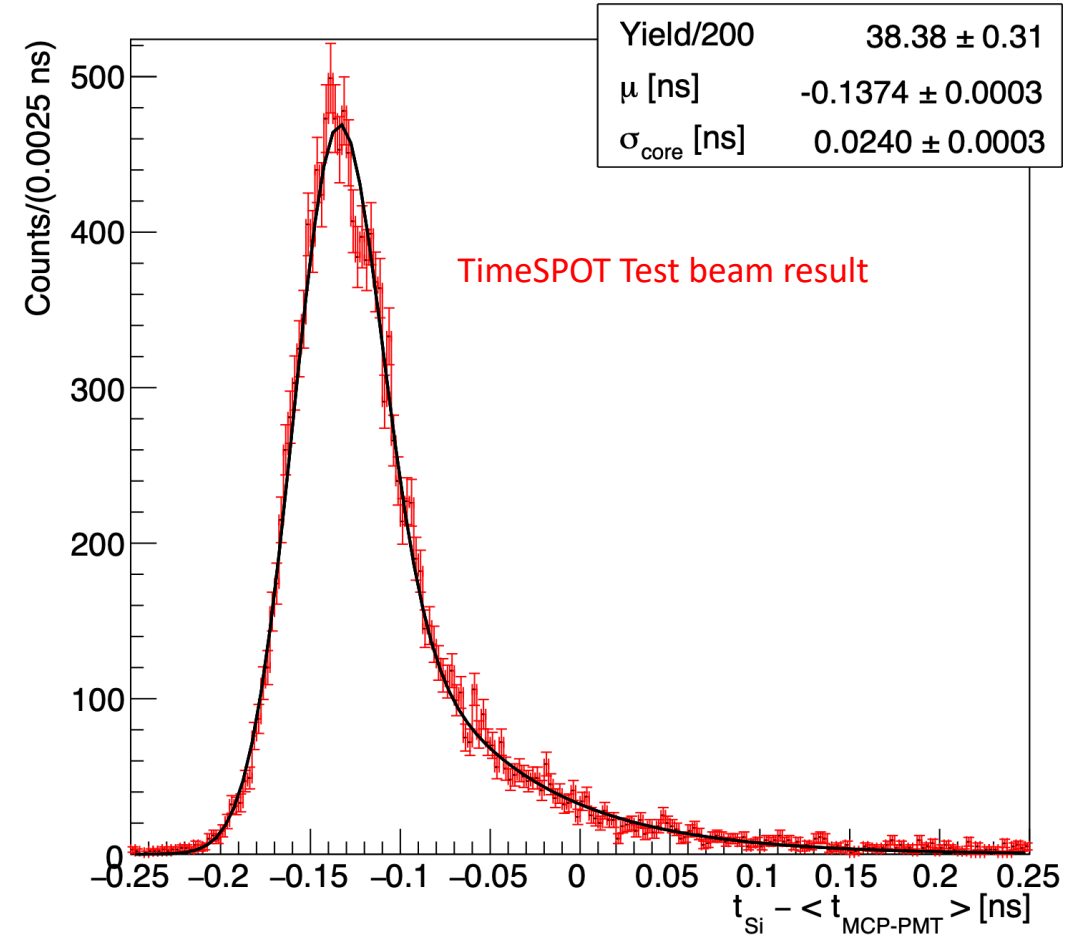
# Why a sensor scan?

In a test beam characterization you only look to the signals that fulfil a trigger condition (in general a threshold in the DUT signal amplitude)

- How do you ensure you are looking at all the sensor active region?



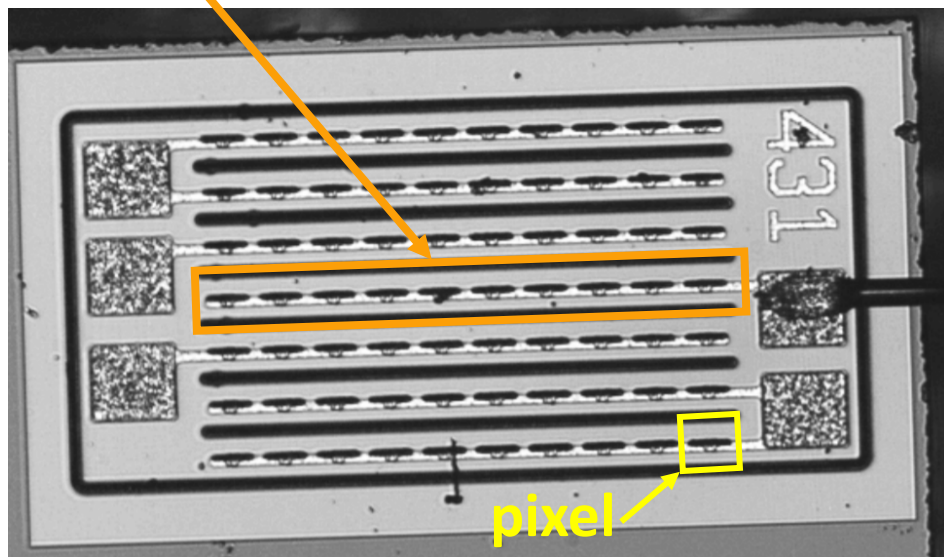
- For trench design we don't expect high disuniformity but is it true also for a more classic 3D geometry?



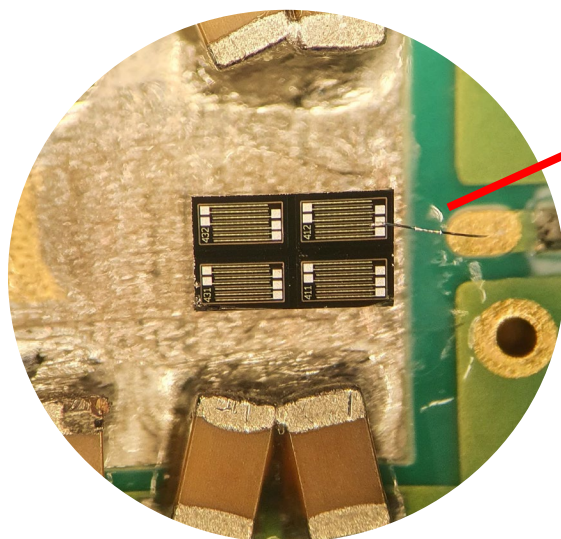
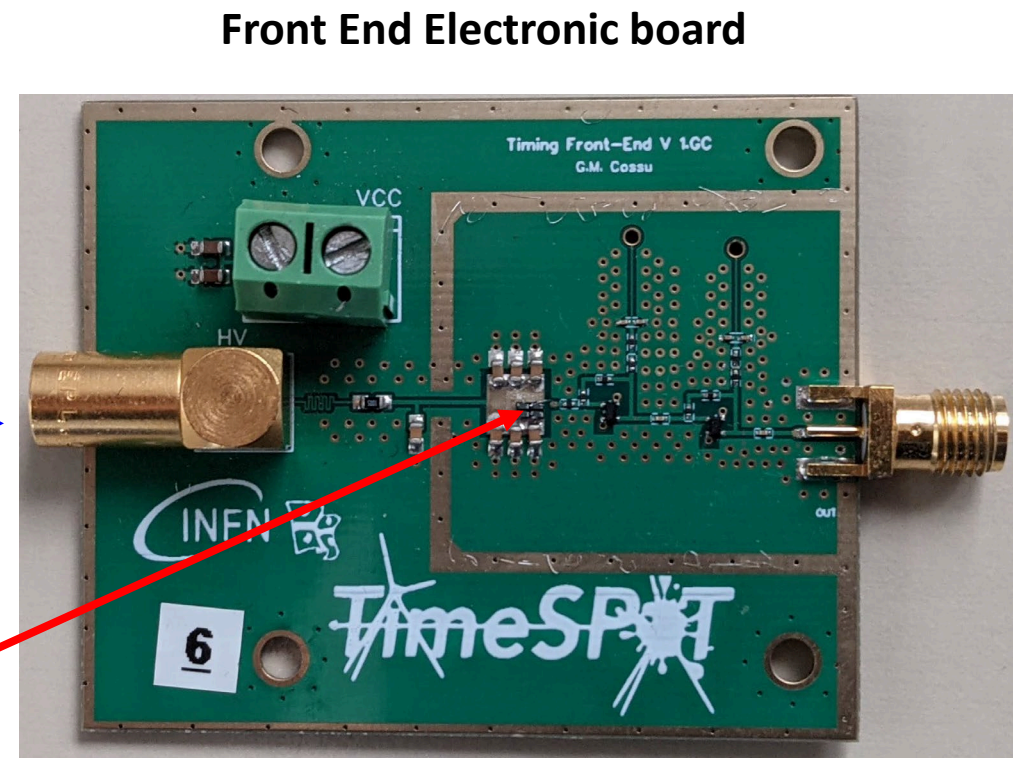
The laser scan allows to measure the **detailed response of the full sensor active area**

# Device Under Test

**PIXEL STRIP:** 10 pixels with readout electrodes shorted together

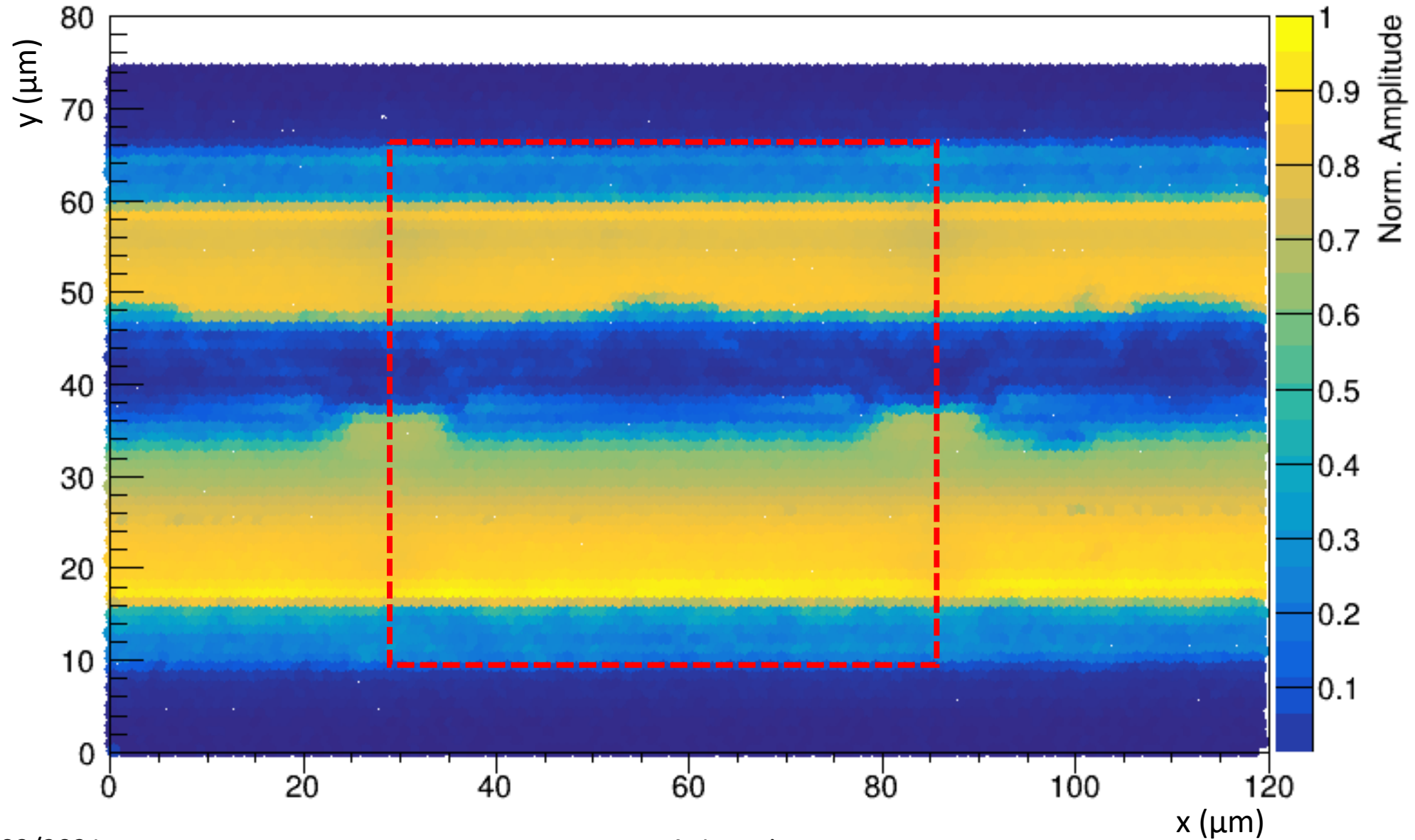


Wire bonding

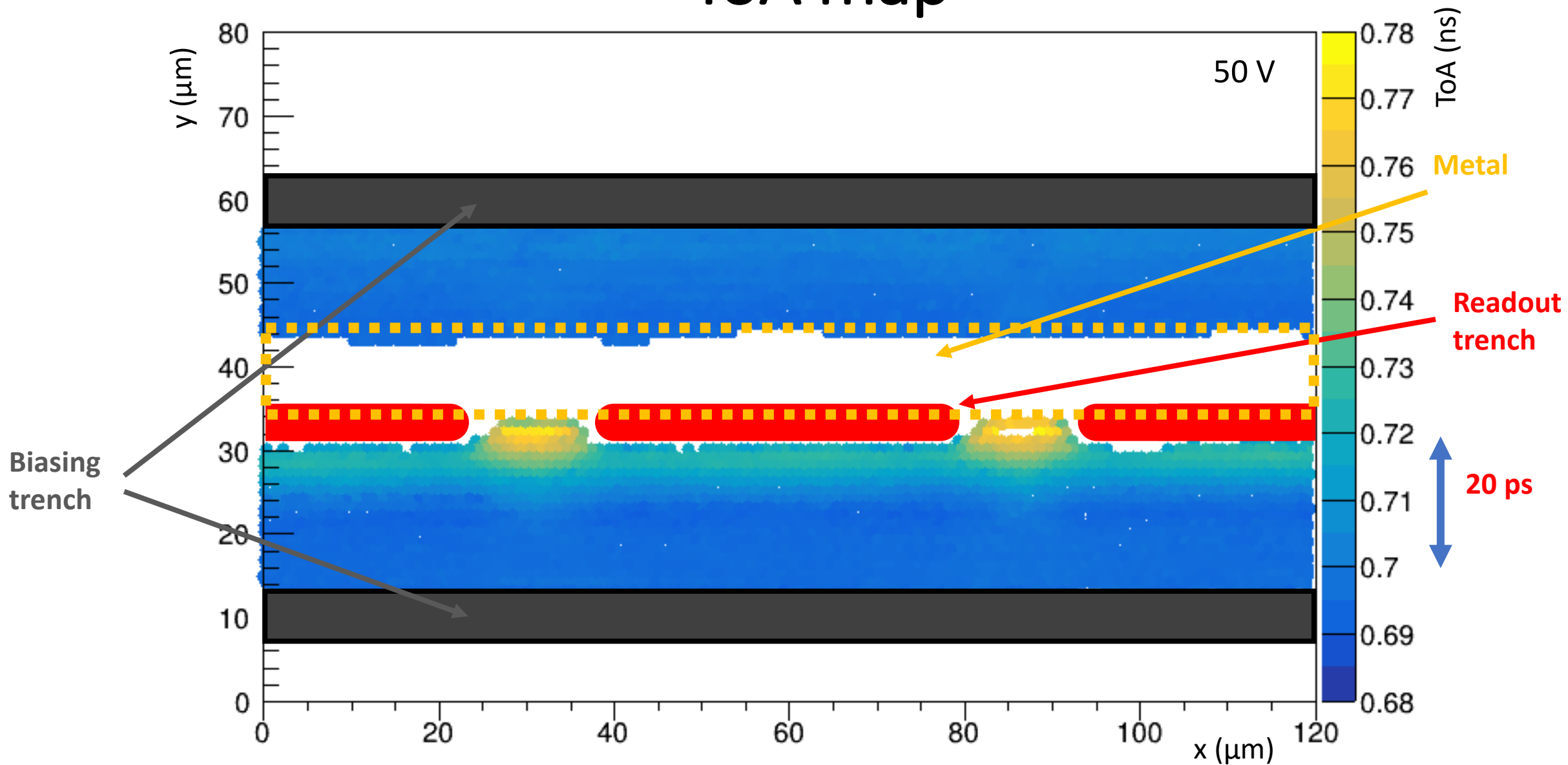


- Electronic **optimized for the TimeSPOT sensors**
- Two stages of **transimpedance amplifier** with ultra low noise SiGe Bjt allows to read very fast sensor's current

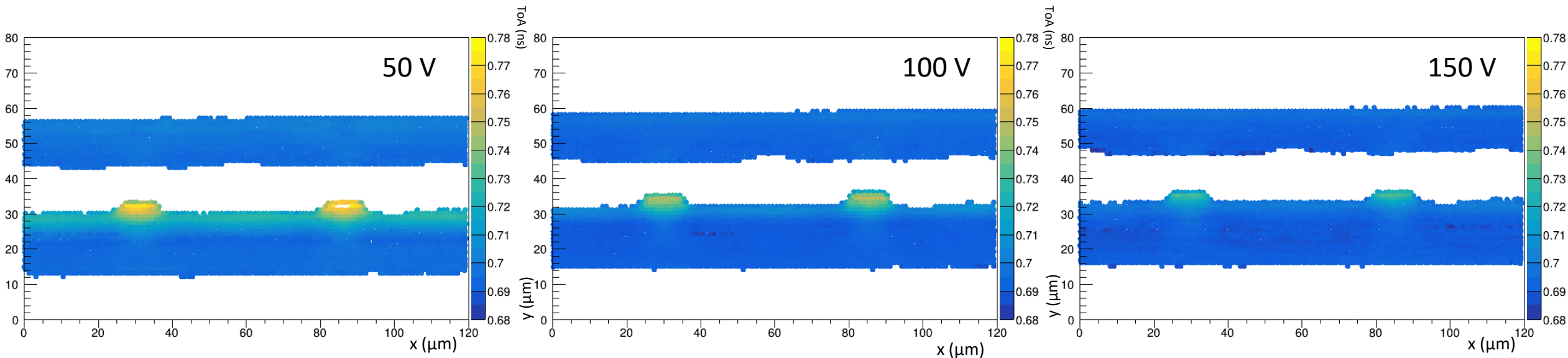
# Amplitude Map



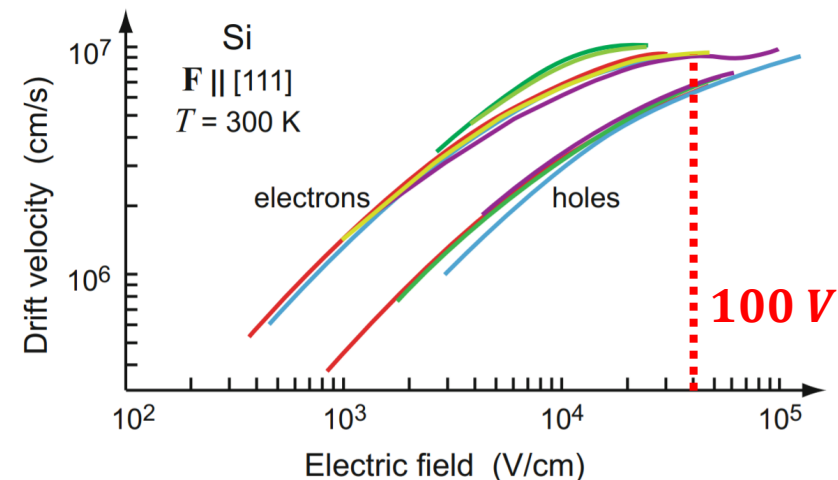
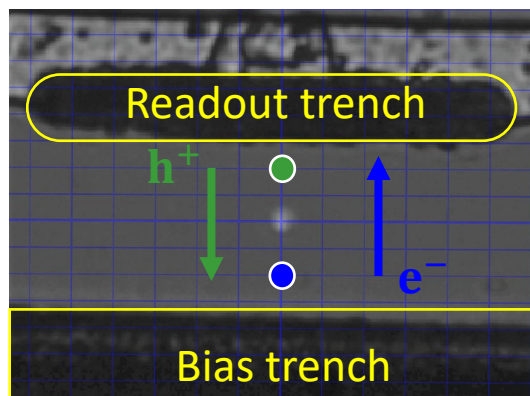
# ToA map



# ToA vs Bias



- Slower regions near the readout trench due to holes drift velocity
- Trend confirmed: as the sensor bias increases the slower zones become faster (the holes drift velocity get closer to saturation)

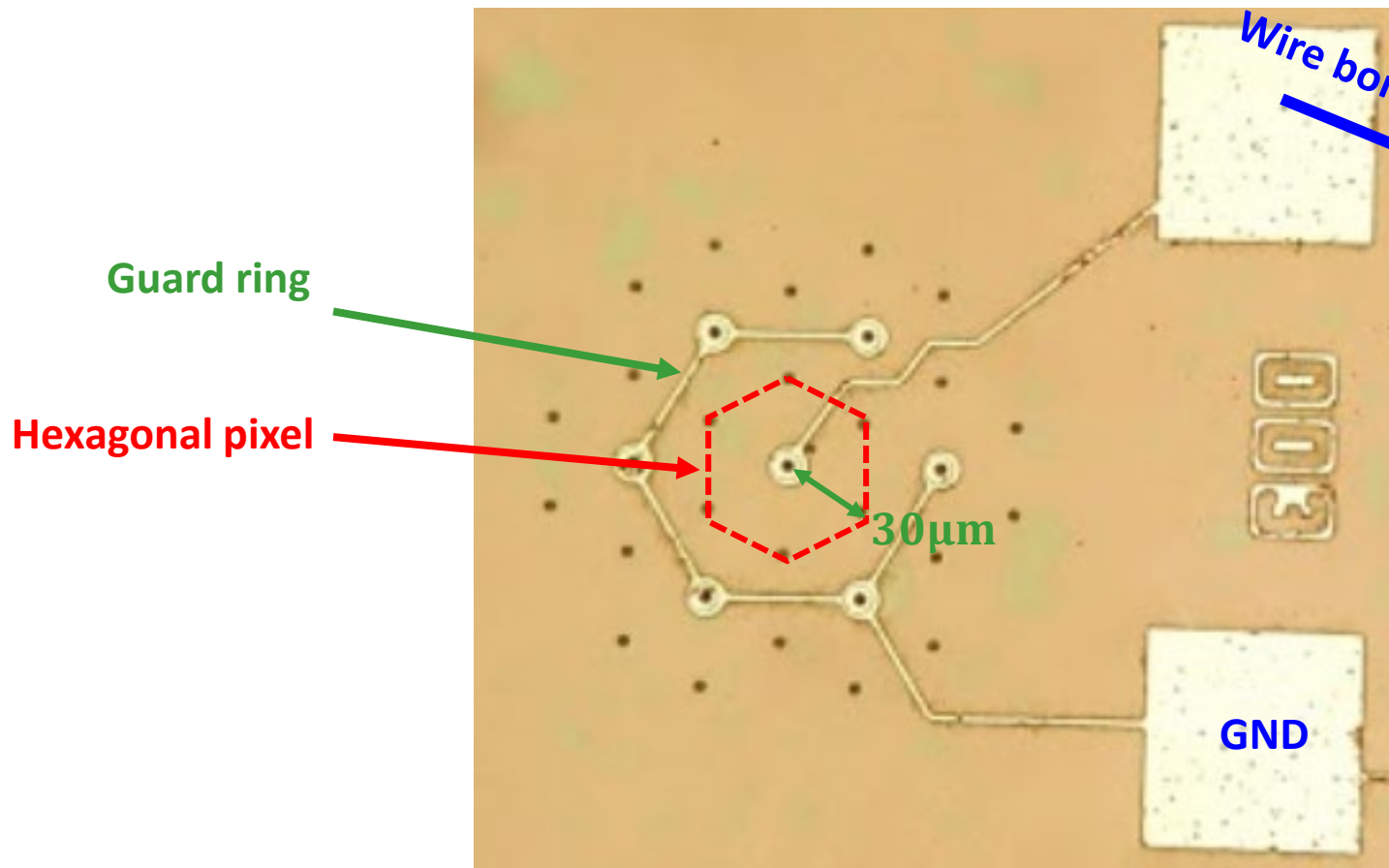


Böer K.W., Pohl U.W. (2018) Carrier Scattering at High Electric Fields. In: Semiconductor Physics. Springer, Cham. [https://doi.org/10.1007/978-3-319-69150-3\\_24](https://doi.org/10.1007/978-3-319-69150-3_24)

Trench pixels produce extremely uniform ToA but increasing the bias voltage they become even more uniform

# Device Under Test: Hexagonal pixel

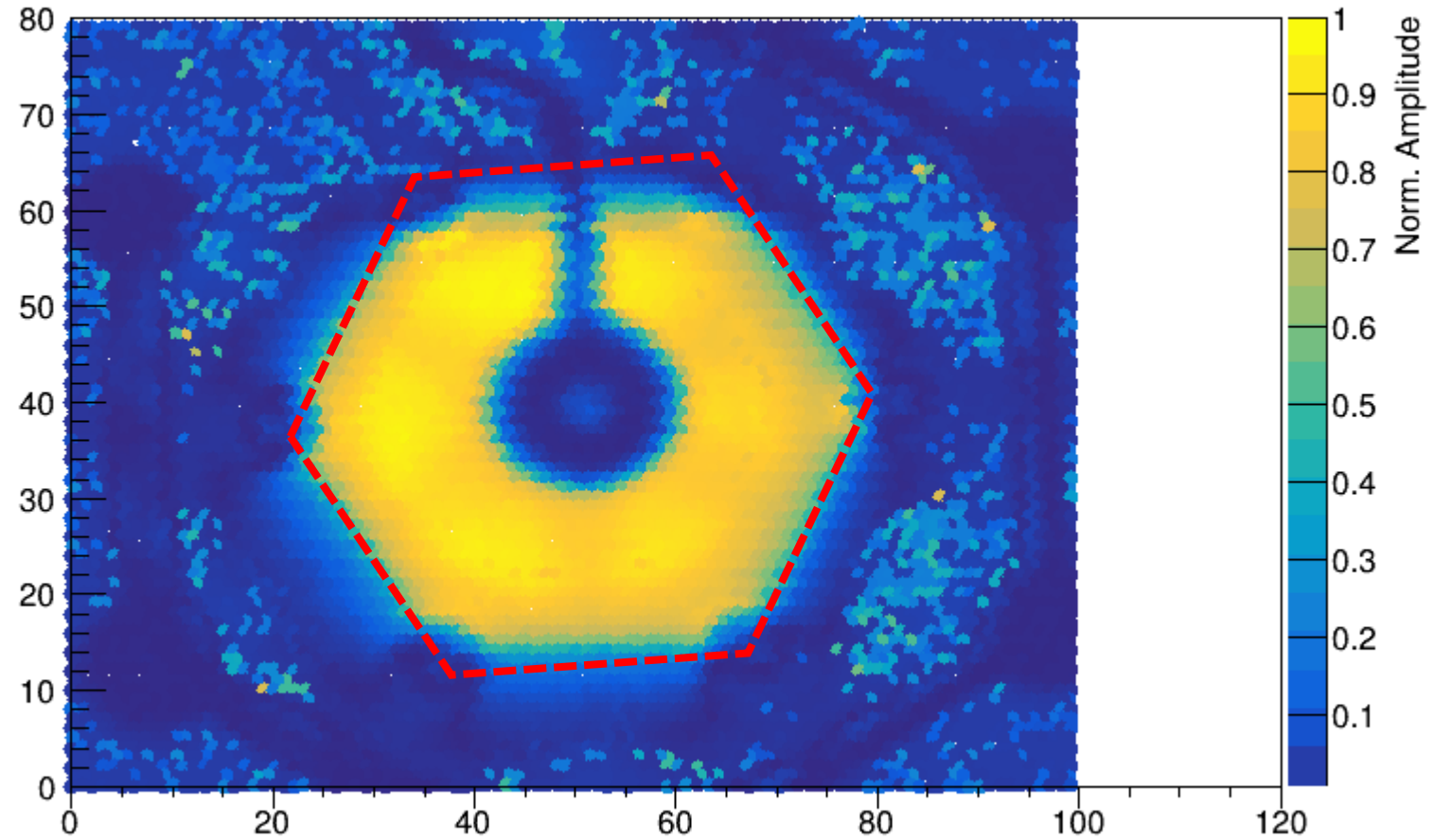
3D column electrodes



- Same front end electronic board

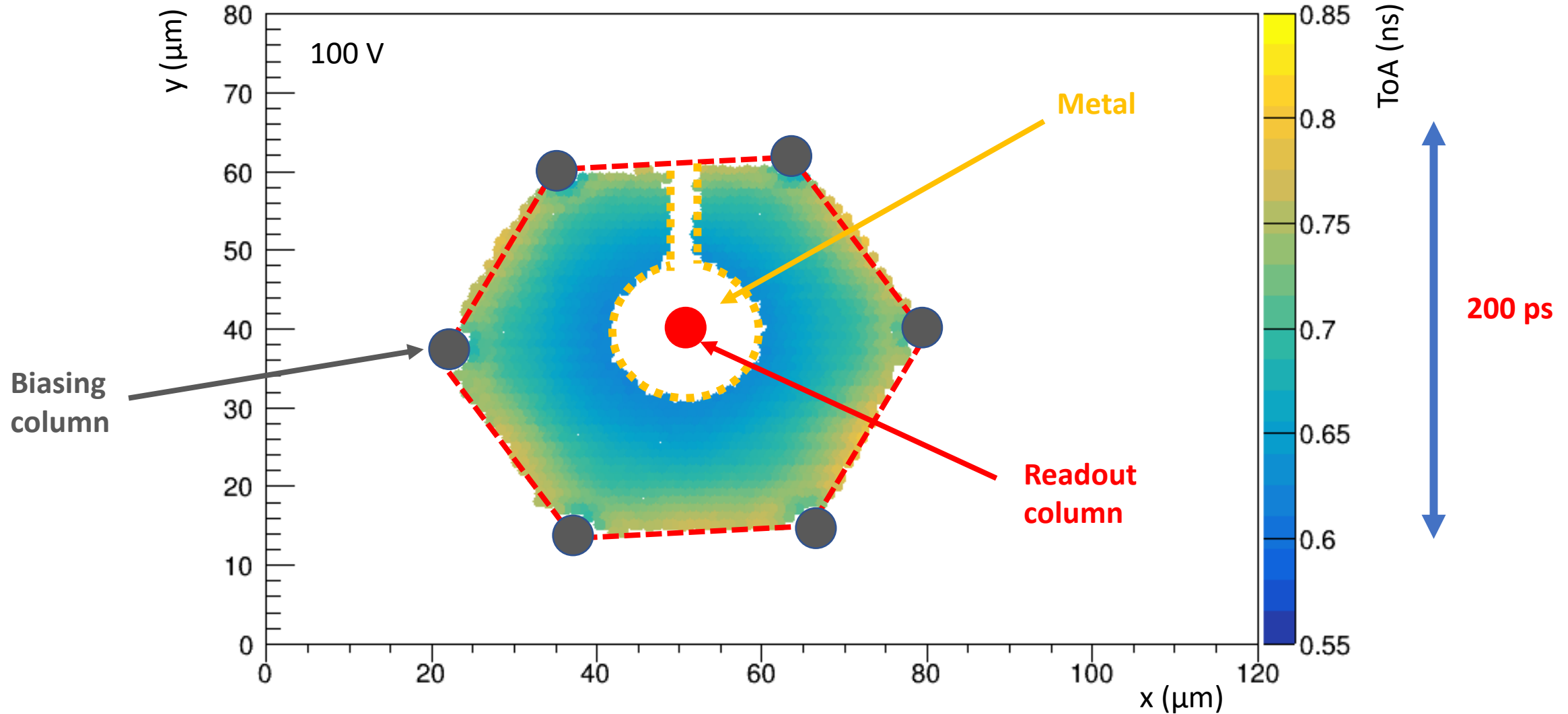
[Sultan, D M S. \(2017\). Development of Small-Pitch, Thin 3D Sensors for Pixel Detector Upgrades at HL-LHC. DOI: 10.13140/RG.2.2.36253.82403/1](https://doi.org/10.13140/RG.2.2.36253.82403/1)

# Amplitude Map: 3D Hexagonal



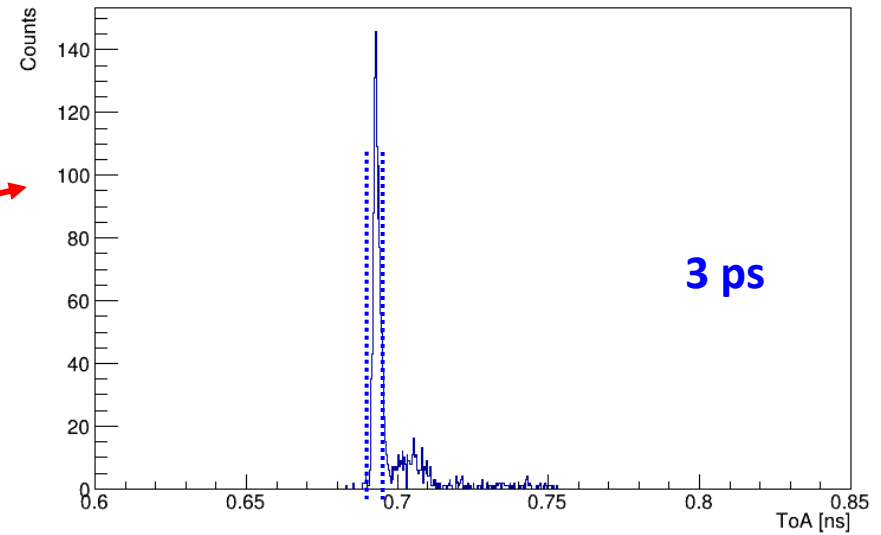
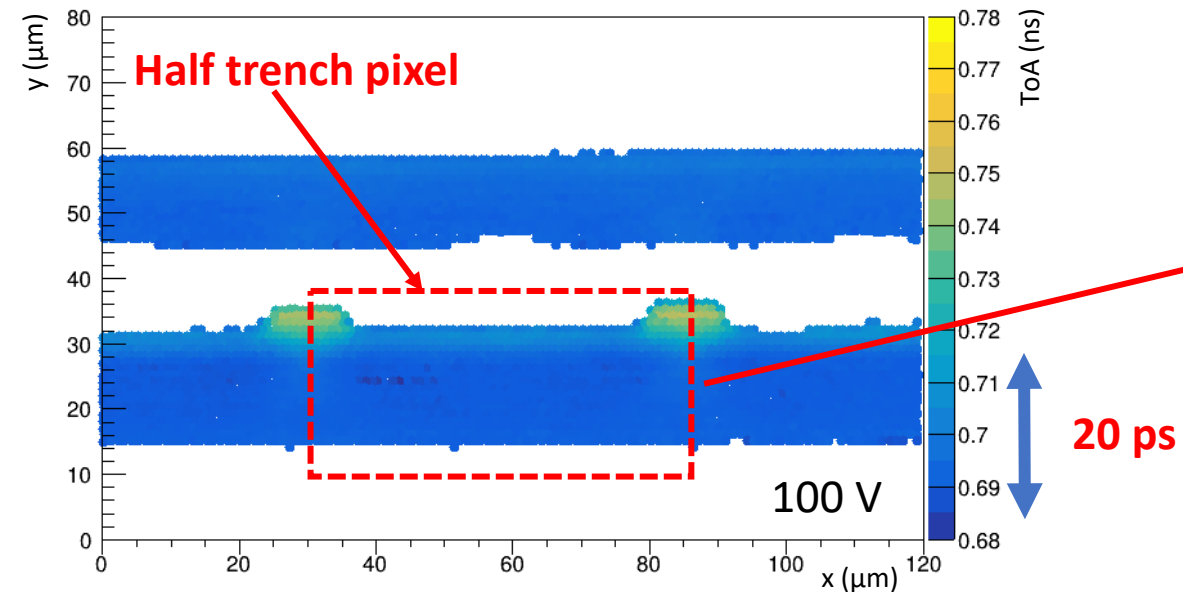


# ToA map: 3D Hexagonal

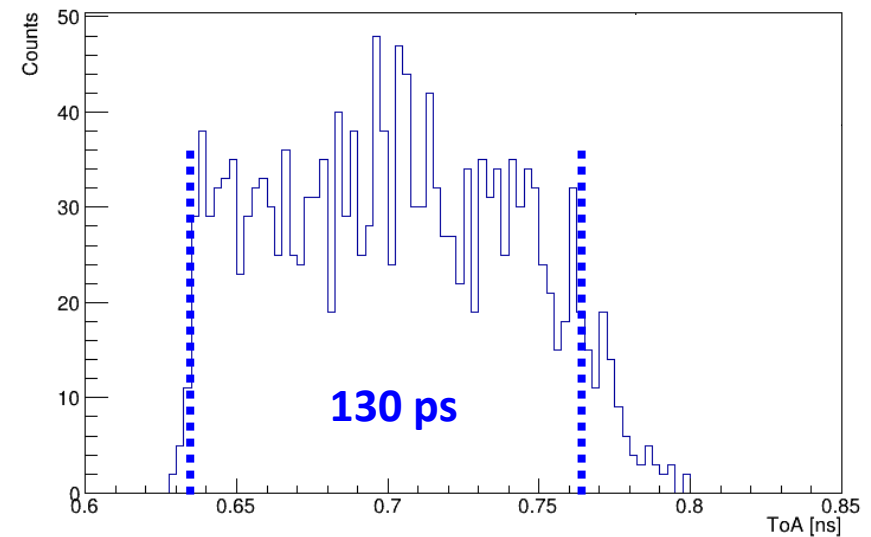
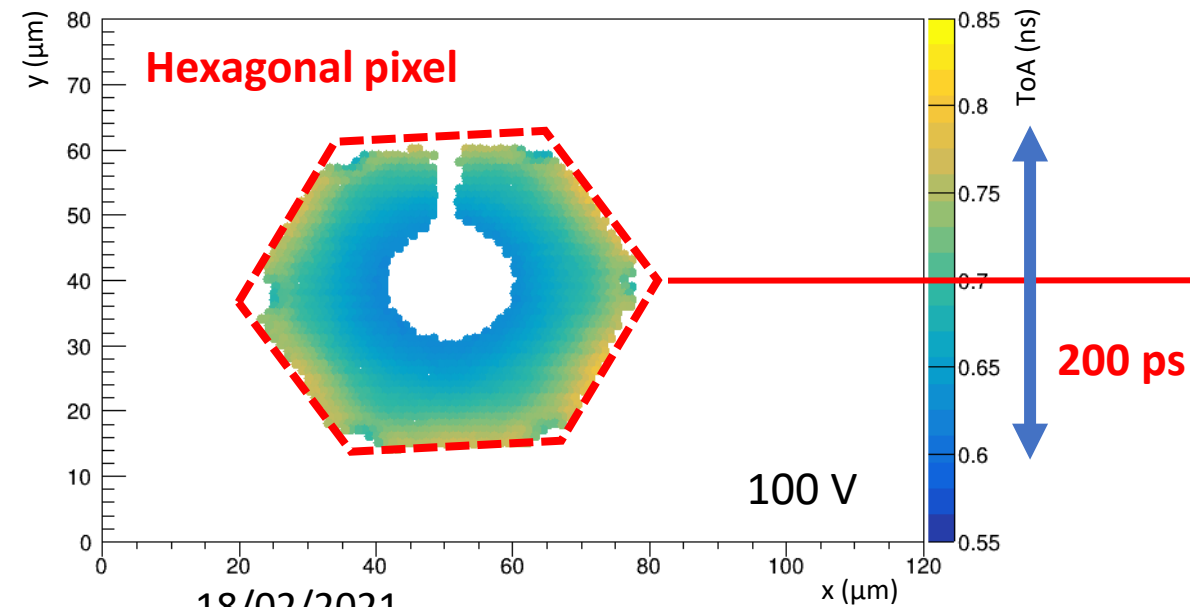


Standard 3D geometry has a very **high spread in ToA**

# Trench vs Hexagonal



For good timing, it's not important to be fast but to be uniform!



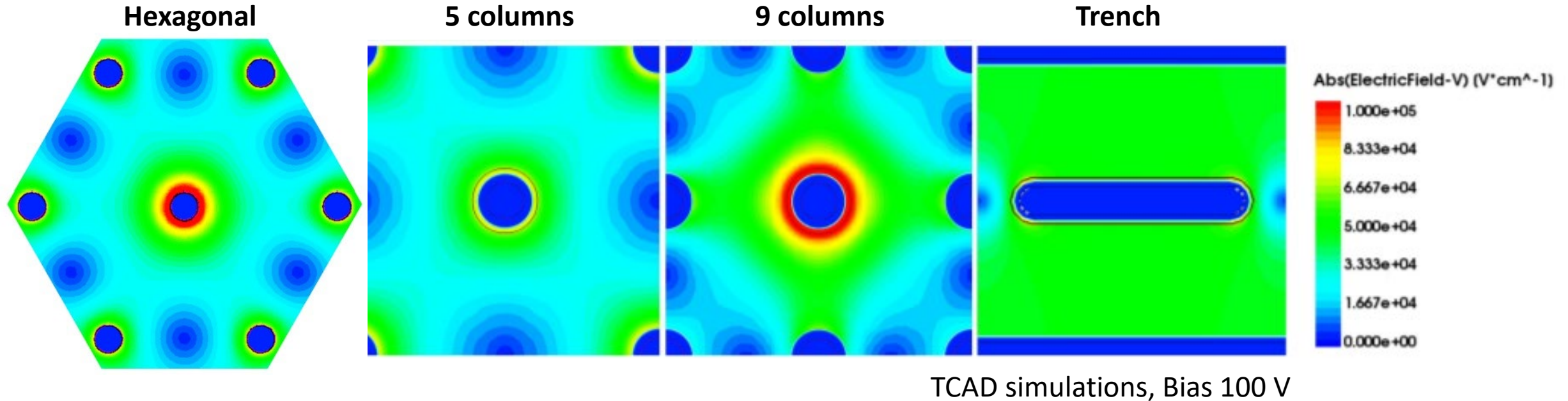
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# Trench vs column

- Electric field maps for several 3D sensors geometries



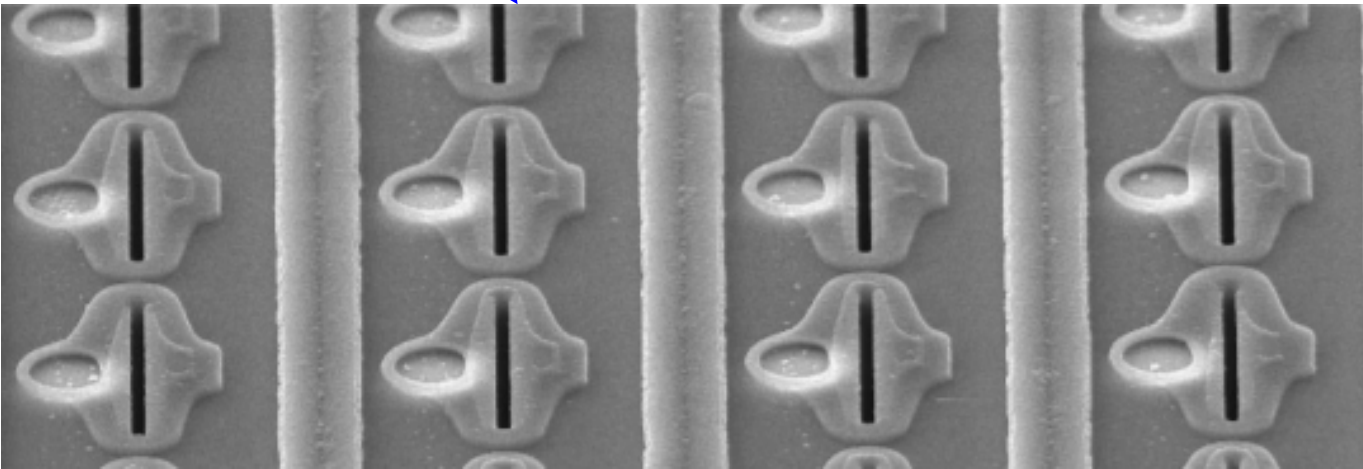
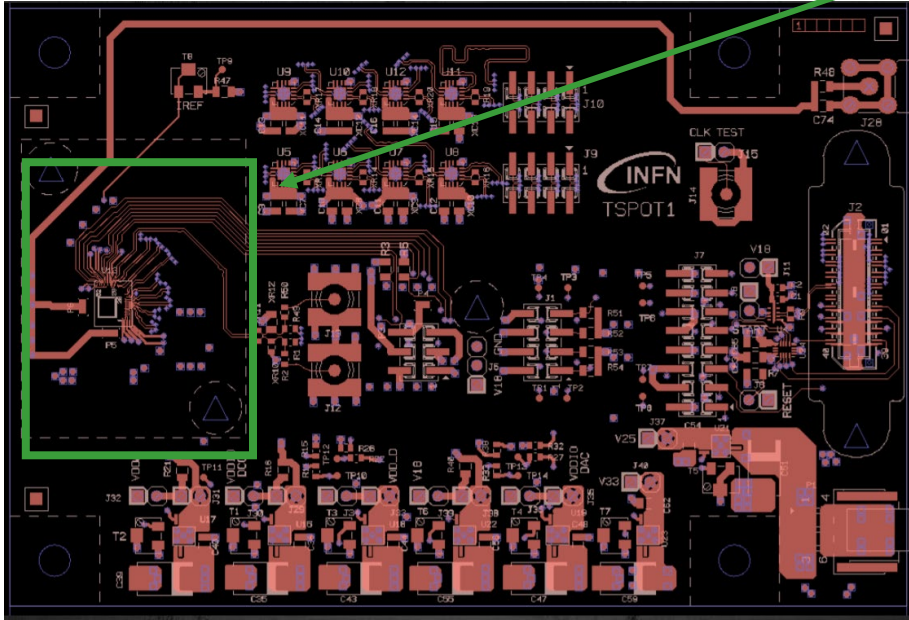
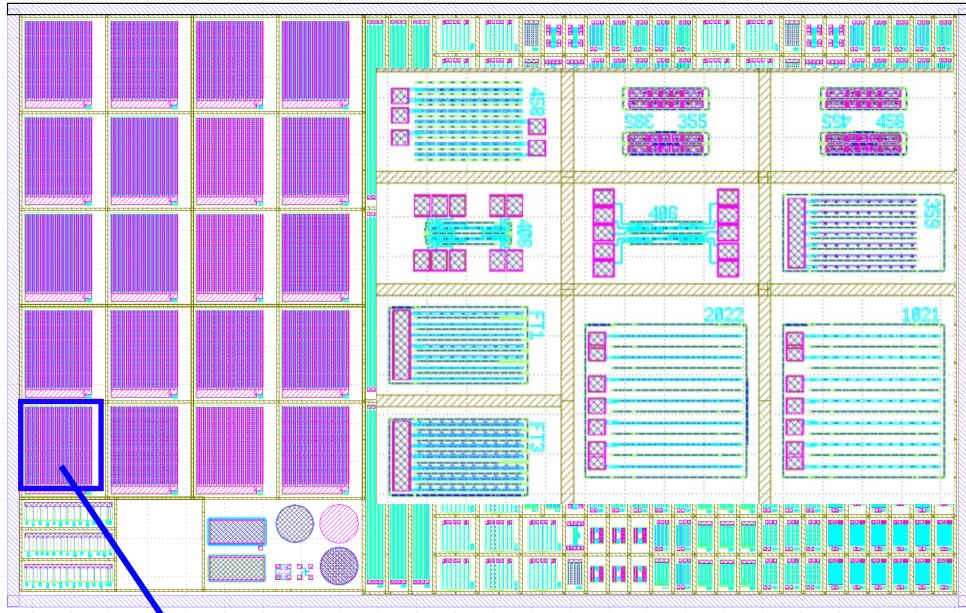
**Electric field** maps are **less uniform** for **all column geometries** with respect to trench design

# Conclusion

- We built a setup that allows to accurately study the timing performances of different sensors geometries
- Unlike test beam and radioactive source characterizations we measured a **detailed response** of the **full sensor active area**
- The **3D trench TimeSPOT sensors** have shown an **excellent timing performance** with respect to more classic 3D geometry

# Outlook

- New sensor production at FBK is completed:
  - New test structures, to continue the characterization of these innovative 3D pixels
  - Matrix of pixels for **bump bonding**
- Characterization of pixels matrix read with **optimized VLSI electronics** (CMOS 28nm)



[S. Cadeddu's talk](#)